

PUBLICATIONS

A) PATENTS

- A1.** “Method for masking silicon during anisotropic wet etching”
P. Normand, K. Beltsios, A. Tserepi, K. Aidinis, D. Tsoukalas
European Patent Application No. 01600006.9-2203, 13-03-01, Publ. No EP1241703, Sept. 2002
- A2.** “Method for the fabrication of suspended porous silicon microstructures and application in gas sensors”
C. Tsamis, A. Tserepi, A. Nassiopoulou
Greek Application No 20010100378, 31-7-2001
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Japan patent (application): Registration Number: 10006875
Publ. No WO 2003/011747, Feb. 2003
- A3.** “Chemically selective capacitive-type sensor and method of fabrication thereof”
S. Chatzandroulis, A. Tserepi, D. Goustouridis, P. Normand, D. Tsoukalas
Greek Patent Appl. No 20010100433, Απνομοή: 2003, No 1004286
- A4.** “Method for the fabrication of high surface area ratio and high aspect ratio surfaces on substrates”
A. Tserepi, E. Gogolides, K. Misiakos, M-E. Vlachopoulou, N. Vourdas
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- A5.** “Bonding method”
K. Misiakos, A. Tserepi, M-E. Vlachopoulou
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- A6.** “Method for making a microarray”
A. Tserepi, E. Gogolides, P. Petrou, S. Kakabakos, P. Bayiati, E. Matrozos
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EPO Patent No & Date: EP2173474, 14.04.2010
- A7.** “Method for Fabrication of Nano-Structures on Polymers using Plasma-directed Self Assembly”
E. Gogolides, A. Tserepi, V. Constantoudis, N. Vourdas, M-E. Vlachopoulou, Greek Patent
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B) Book editing

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Γ) ARTICLES IN PEER-REVIEWED JOURNALS

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- 23. Surface modification of Si-containing polymers during etching for bilayer lithography**
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- 28. Fabrication of suspended thermally insulating membranes using front-side micromachining of the Si substrate: characterization of the etching process**
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- 42.** *Monolithic silicon optoelectronic transducers and elastomeric fluidic modules for bio-spotting and bio-assay experiments*
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- 43.** *Alternative micro-hotplate design for low power sensor arrays*
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- 44.** *A review of line-edge roughness and surface nanotexture resulting from patterning processes*
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